

Form PTO-1449				ATTY. DOCKET NO. 0171-1058P		APPLICATION NO. NEW	
INFORMATION DISCLOSURE CITATION IN AN APPLICATION (Use several sheets if necessary)				APPLICANT HATAKEYAMA, Jun et al			
				FILING DATE January 29, 2004		GROUP	

U.S. PATENT DOCUMENTS							
EXAMINER INITIAL	DOCUMENT NUMBER	Kind	DATE	NAME	CLASS	SUB CLASS	FILING DATE IF APPROPRIATE
SJL ↓	US 4,491,628		1985-01-01	Ito et al.	430	176	
	US 5,310,619	A	1994-05-10	Crivello et al.	430	270.1	
	US 6,492,089	B2	2002-12-10	Hatakeyama et al.	430	270.1	
	US 2003/0224291	A1	2003-12-4	Hatakeyama et al.	430	270.1	

FOREIGN PATENT DOCUMENTS									
	Office	DOCUMENT NUMBER	Kind	DATE	COUNTRY	CLASS	SUB CLASS	TRANSLATION	
								YES	NO
SJL ↓	JP	2-27660	B2	1990-06-19	JAPAN			ABS	
	JP	63-27829	A	1988-02-05	JAPAN			ABS	
	JP	9-73173	A	1997-03-18	JAPAN			ABS	
	JP	10-10739	A	1998-01-16	JAPAN			ABS	
	JP	9-230595	A	1997-09-05	JAPAN			ABS	
	WO	97/33198		1997-09-12	WO				
	JP	6-118651	A	1994-04-28	JAPAN			ABS	
	JP	10-324748	A	1998-12-08	JAPAN			ABS	
	JP	11-302382	A	1999-11-02	JAPAN			ABS	
	JP	2002-055456	A	2002-2-20	JAPAN			ABS	
	JP	9-110938	A	1997-4-28	JAPAN			ABS	
	JP	2001-278918	A	2001-10-10	JAPAN			ABS	
	JP	2001-158808	A	2001-6-12	JAPAN			ABS	

OTHER DOCUMENTS	
(Include Name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.) date, page(s), volume-issue number(s), publisher, city and/or country where published.)	
SJL ↓	International Work Shop 157nm Lithography MIT-LL, Boston, MA May 5, 1999
	Kunz et al., Outlook for 157 nm resist design, J. Vac. Sci. Technol., B17 (6), Nov/Dec 1999, pp. 3267-3272
	Chiba et al., 157nm Resist Materials; A Progress Report, J. Photopolymer Sci. and Technol., Vol. 13, No. 4 (2000) pp. 657-664
	Schmaljohann et al., Fundamental Studies of Fluoropolymer Photoresists for 157 nm Lithography, J. Photopolymer Sci. and Technol., Vol. 13, No. 3 (2000) pp. 451-458
EXAMINER <i>S. J. Lu</i> DATE CONSIDERED <i>12-25-2005</i>	

EXAMINER: Initial if citation considered, whether or not citation is in conformance with M.P.E.P. 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

6/24/2011